

Electronic Supplementary Information for JMCC

**SUPPORTING INFORMATION**

**Flexible Inkjet Printed high-k HfO<sub>2</sub>-Based MIM Capacitors**

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***This PDF file includes:***

Figs. S1 to S08

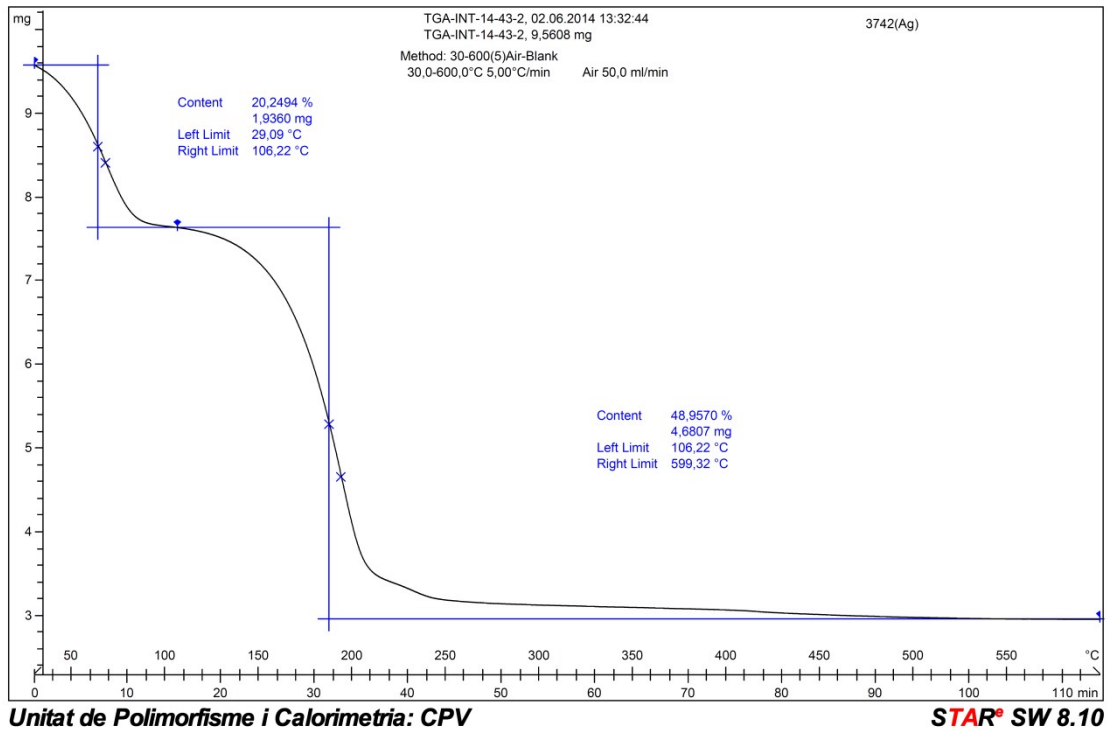
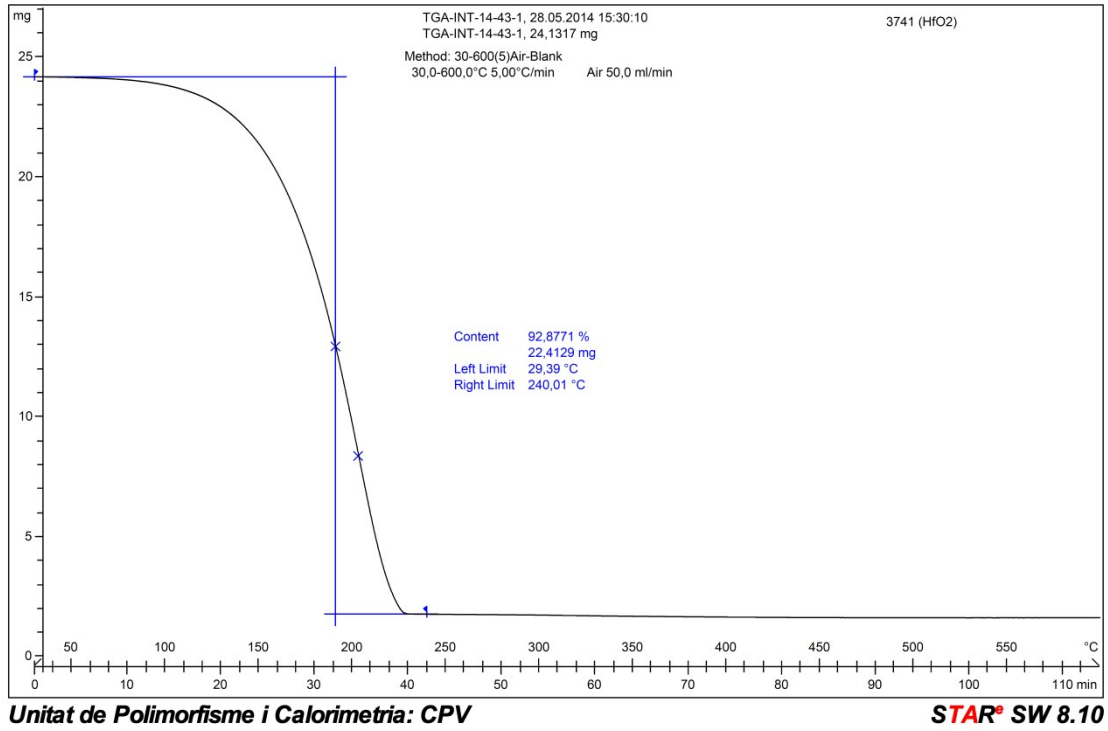


Fig. S1 Thermogravimetry analysis (TGA) of HfO<sub>2</sub> and Ag inks.

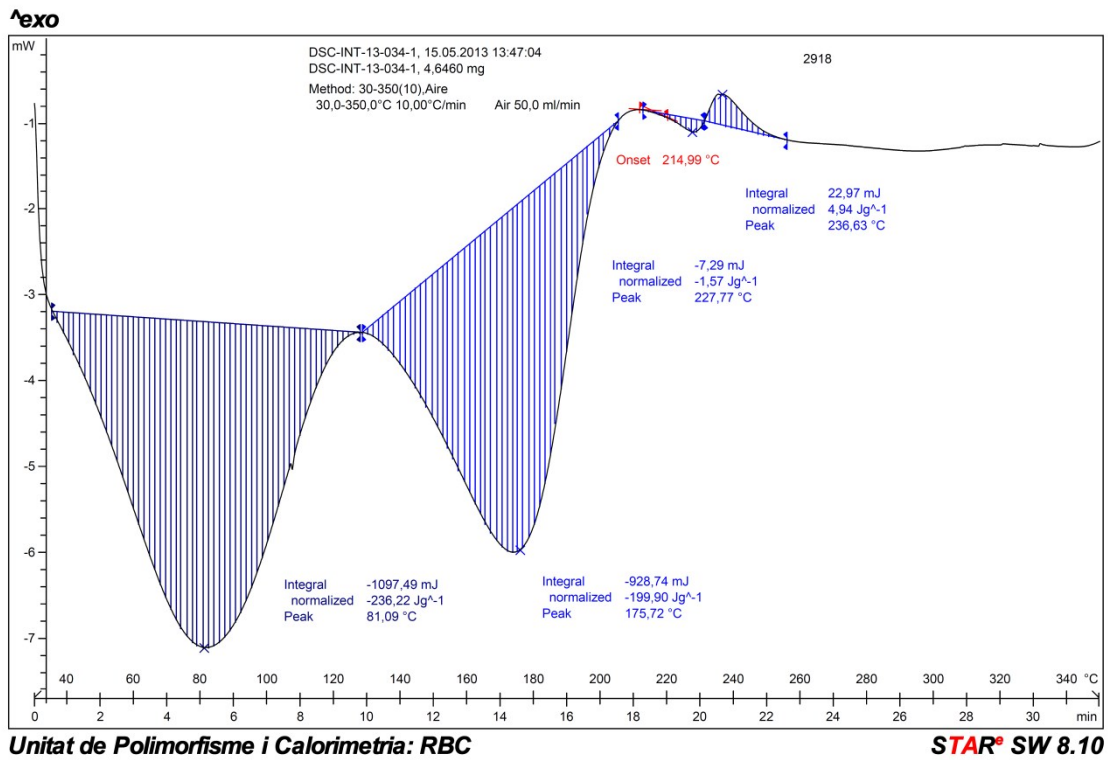
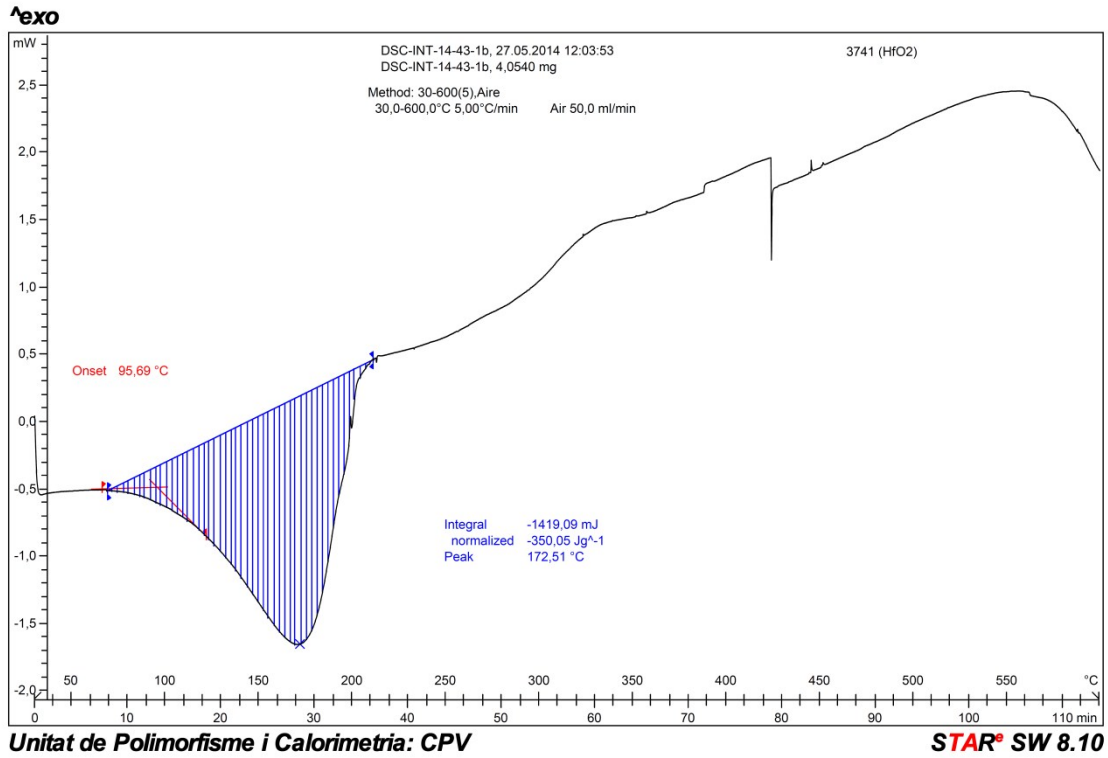
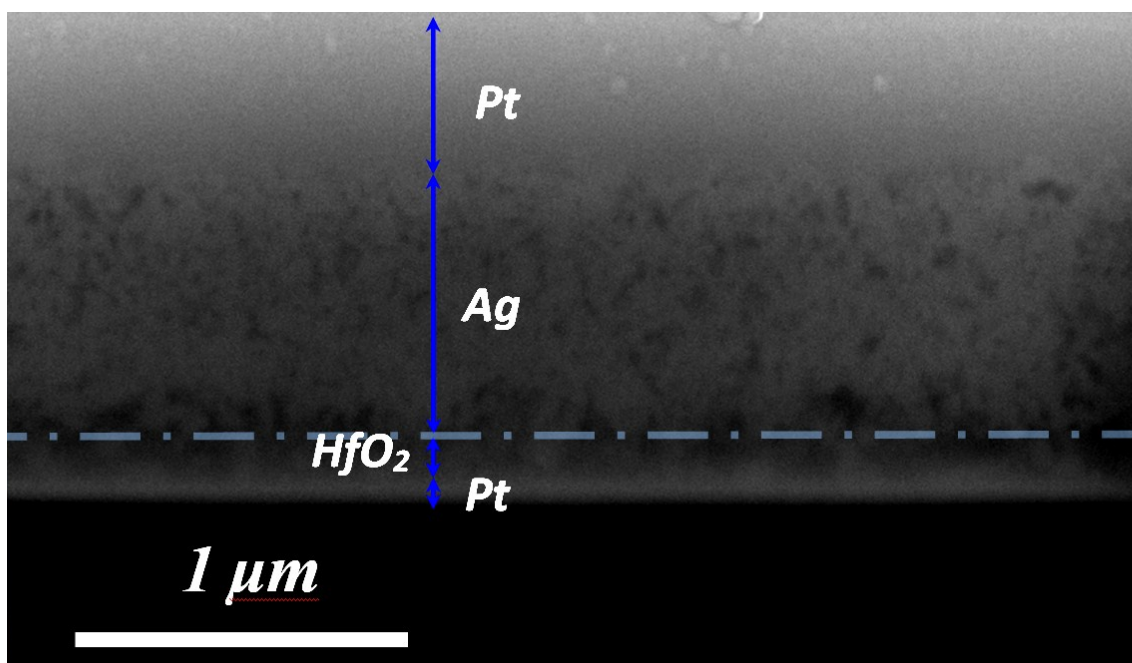
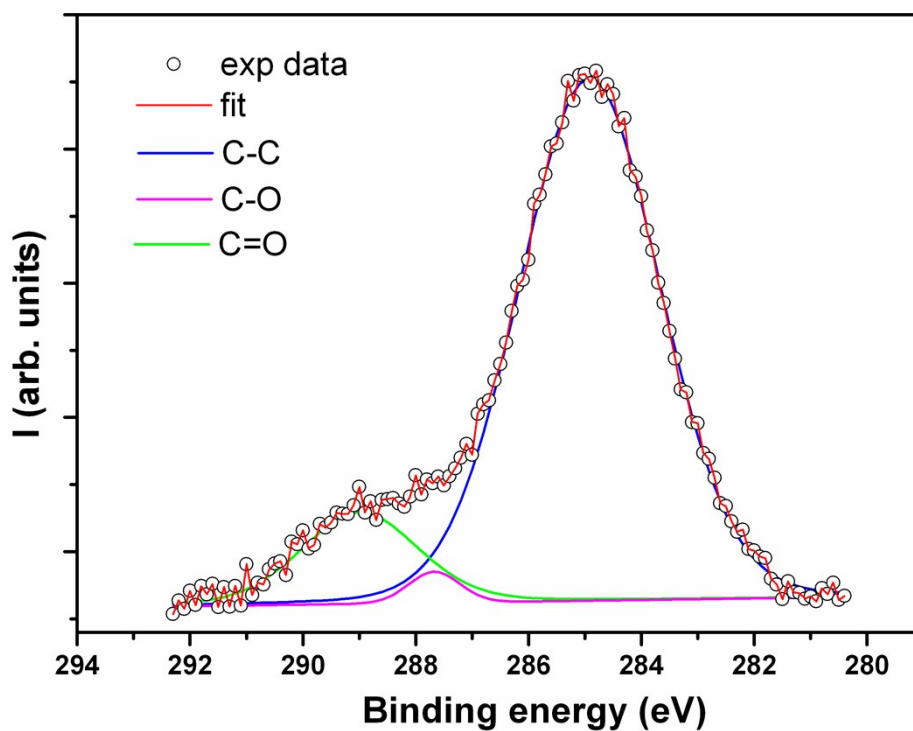


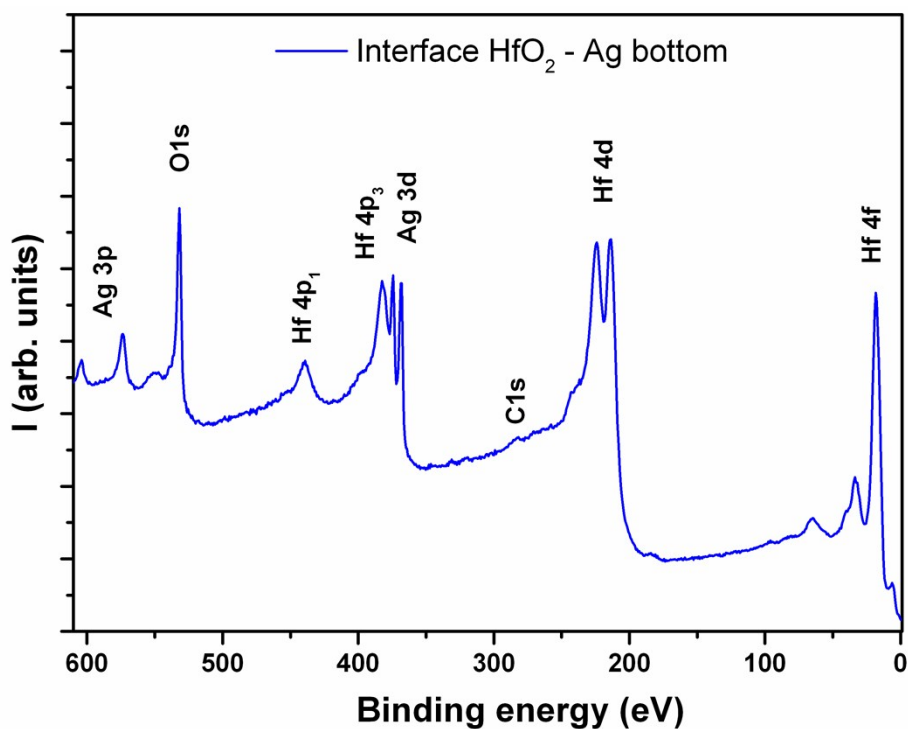
Fig. S2 Differential scanning calorimetry (DSC) measurement of HfO<sub>2</sub> and Ag inks.



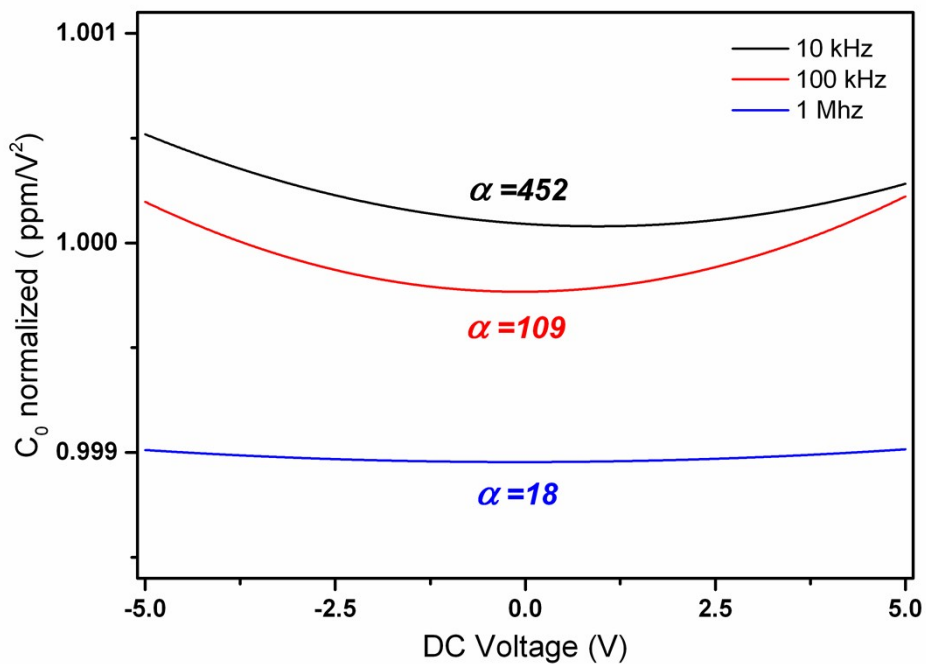
**Fig. S3** Cross-section of MIM capacitor by FIB-assisted FE-SEM technique. The as-deposited layers have a Pt bottom electrode thickness of 50 nm, 120 nm for HfO<sub>2</sub> and 700 nm of Ag top contact.



**Fig. S4** XPS Binding Energy High-Resolution spectra of C in annealed HfO<sub>2</sub> thin film at 250 °C for 2 h, deposited on Ag bottom contact. The curve represents the experimental data with the corresponding peaks fitting.

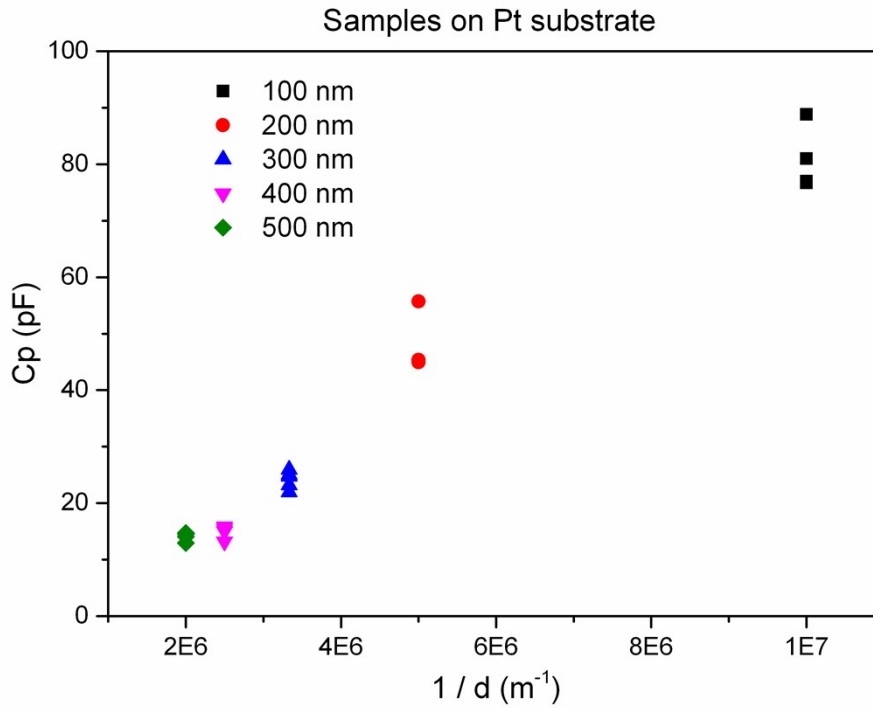


**Fig. S5** XPS Binding Energy Survey spectra at the interface of the structure HfO<sub>2</sub>/Ag bottom contact.

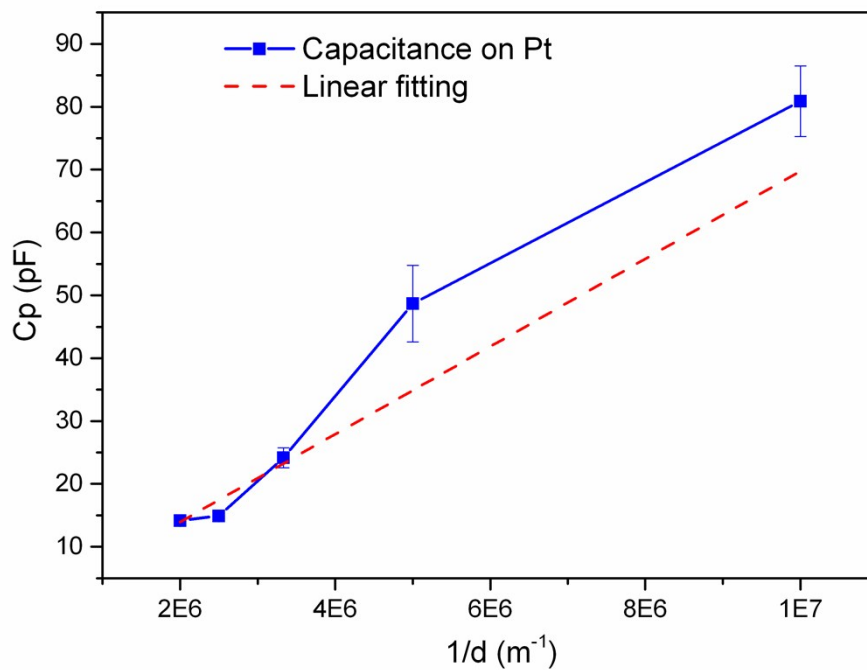


**Fig. S6** Normalized capacitance-frequency dependence of an inkjet-printed Ag/HfO<sub>2</sub>/Ag MIM capacitor.

a)

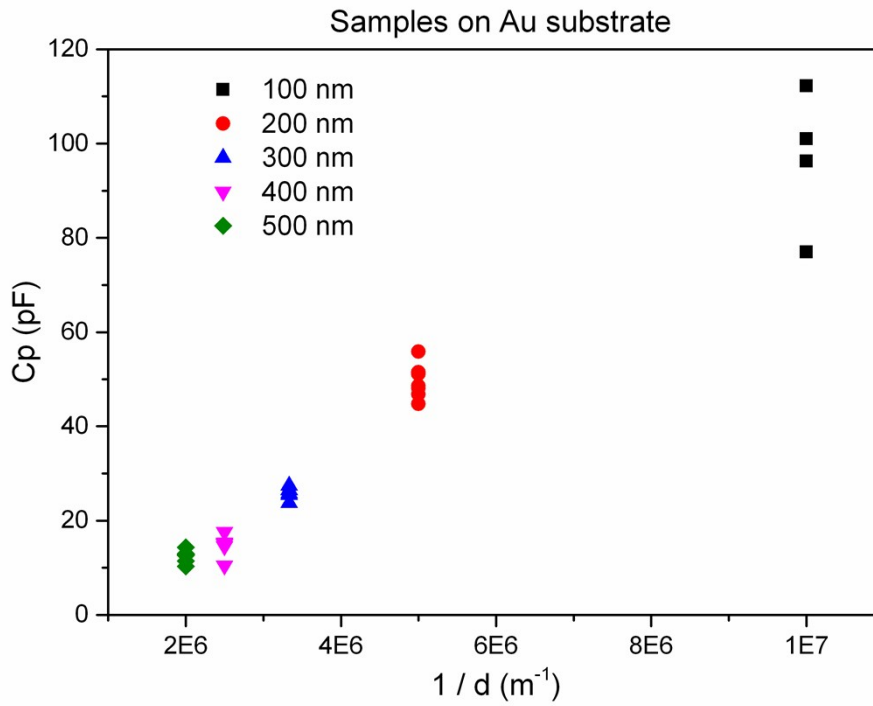


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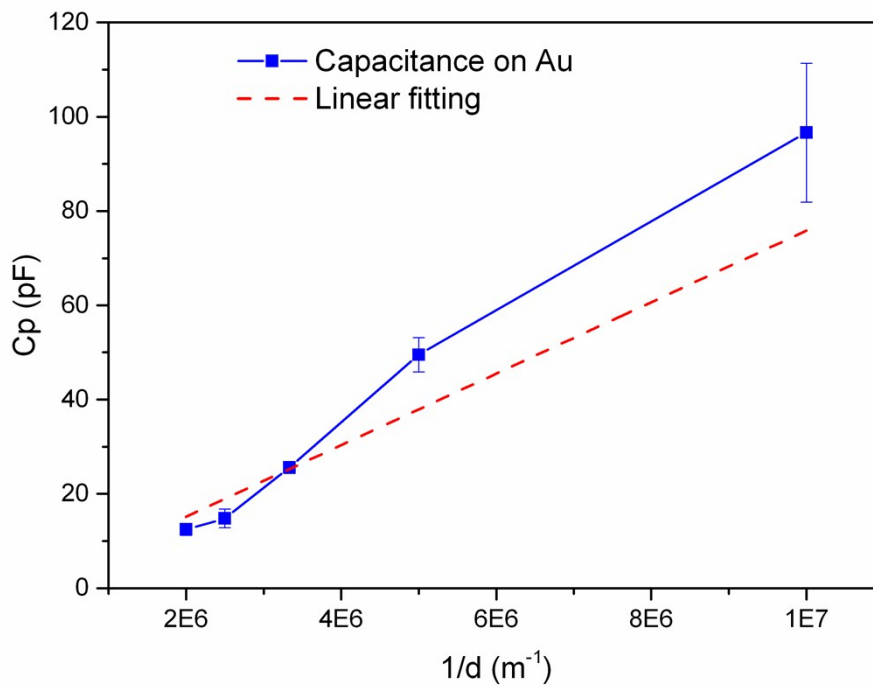


**Fig. S7 (a)** MIM capacitors structure Ag / HfO<sub>2</sub> / Pt with different thickness. **(b)** Linear fitting and curve regression for evaluation of dielectric constant.

*a)*



*b)*



**Fig. S08** (a) MIM capacitors structure Ag / HfO<sub>2</sub> / Au with different thickness. (b) Linear fitting and curve regression for evaluation of dielectric constant.